Rev. 1-10-03 Effective March 1998

DECLARATION AND POWER OF ATTORNEY FOR U.S. PATENT APPLICATION

() Original () Supplemental () Substitute (X) PCT () DESIGN

As a below named inventor, I hereby declare that: my residence, post office address and citizenship are as stated below next to my name; that I verily believe that I am the original, first and sole inventor (if only one name is listed below) or an original, first and joint inventor (if plural inventors are named below) of the subject matter which is claimed and for which a patent is sought on the invention entitled:

Title: MATERIAL FOR FORMING RESIST PROTECTIVE FILM FOR LIQUID IMMERSION LITHOGRAPHY PROCESS, RESIST PROTECTIVE FILM FORMED BY THE MATERIAL, AND METHOD OF FORMING RESIST PATTERNS USING THE MATERIAL

f which is described and claimed in:) the attached specification, or) the specification in application Ser	ial No,	filed	, and	with amendments	
hrough, or X) the specification in International	Application No. PCT/JP2004/012	204, filed <u>Augus</u>	t 25, 2004, and as amen	ded on _(if applicabl	
hereby state that I have reviewed an ny amendment(s) referred to above.					
acknowledge my duty to disclose to t n Title 37, Code of Federal Regulation	he Patent and Trademark Office all ons, §1.56.	l information kno	wn to me to be material to	patentability as def	
hereby claim priority benefits under for patent or inventor's certificate listed iling date before that of the application	ed below and have also identified	(and §172 if this below any applic	application is for a Desigation for patent or inven	gn) of any applicatio tor's certificate havi	
COUNTRY	APPLICATION NO.	D	ATE OF FILING	PRIORITY CLAIMED	
Japan	2003-300666	A	ugust 25, 2003	YES	
Japan	2003-356963	o	ctober 16, 2003	YES	
hereby claim the benefit under Title ubject matter of each of the claims of irst paragraph of Title 35, United Sta n Title 37, Code of Federal Regulati nternational filing date of this applic	this application is not disclosed in ates Code §112, I acknowledge the ons, §1.56 which occurred between	n the prior United e duty to disclose	States application in the information material to	manner provided by patentability as def	
	. U.S. FILING D	U.S. FILING DATE STATUS		: PATENTED, PENDING, ABANDONED	
APPLICATION SERIAL NO			ABANDO		

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Patent and Trademark Office connected therewith.

I hereby authorize the U.S. attorneys and agents named herein to accept and follow instructions from <u>Sakai International Patent Office</u> as to any action to be taken in the U.S. Patent and Trademark Office regarding this application without direct communication between the U.S. attorneys and myself. In the event of a change in the persons from whom instructions may be taken, the U.S. attorneys named herein will be so notified by me.

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I further declare that all statements made herein of my own knowledge are true, and that all statements on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

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The above application may be more particularly identified	as follows:
U.S. Application Serial No.	Filing Date February 22, 2006
Applicant Reference Number PTKA-04109-US (IMM-TC	25/PCT) Atty Docket No. 2006-0227A

Title of Invention MATERIAL FOR FORMING RESIST PROTECTIVE FILM FOR LIQUID IMMERSION LITHOGRAPHY PROCESS, RESIST PROTECTIVE FILM FORMED BY THE MATERIAL, AND METHOD OF FORMING RESIST PATTERNS USING THE MATERIAL